## Spin-orbit torque induced switching of antiferromagnet/non-magnet metallic structure °S. DuttaGupta<sup>1-3</sup>, A. Kurenkov<sup>1-3</sup>, O. A. Tretiakov<sup>6</sup>, G. Krishnaswamy<sup>7</sup>, G. Sala<sup>7</sup>, V. Krizakova<sup>7</sup>, F. Maccherozzi<sup>8</sup>, S. S. Dhesi<sup>8</sup>, P. Gambardella<sup>7</sup>, S. Fukami<sup>1-5</sup> and H. Ohno<sup>1-5</sup>

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Utilization of antiferromagnets (AFMs) as active components of spintronic devices offers several unique advantages complementing current ferromagnet (FM) based spintronic architectures [1-8]. The capability of electrical writing and reading is crucial for the development of AFM-based spintronic devices [4-7]. One of the possible candidates satisfying the requirement is Mn-based metallic alloys (Mn-X where X = 4d/5d metal). In our previous work, we have demonstrated magneto-resistive effects in an AFM/heavy-metal (HM) PtMn/Pt structure [8], which offers electrical reading scheme of stored information without auxiliary FMs. Here, we demonstrate electrical writing of PtMn/Pt by spin-orbit torques.

The multilayer films with stack structures sub./buffer/PtMn(10)/Pt(5)/Ru(1) (PtMn/Pt, hereafter) (in nm) are grown by sputtering and patterned into star-shaped devices. Electrical writing is achieved by applying pulsed

currents ( $I_{Write}^{1}$  and  $I_{Write}^{0}$ ) along orthogonal directions, while read-out is achieved by measuring transverse Hall resistance  $R_{Hall}$ (Fig. 1(a),(b)). Figure 1(c) shows the results of electrical writing for different current amplitudes. A combination of electrical measurements with X-ray magnetic imaging on similar structures shows a reorientation of antiferromagnetic Néel vector upon application of  $I_{Write}^{1}$  and/or  $I_{Write}^{0}$ .

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Figure 1: Schematic diagram of measurement. (a) Writing scheme under  $I_{Write}^1$  and/or  $I_{Write}^0$ . (b) Read-out by measuring transverse voltage ( $V_{DC}$ ) under application of read current. (c) Electrical writing in PtMn/Pt for different current density in Pt layer.

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